



# WP4 Photonics Components for pre- and post- pulse conditioning

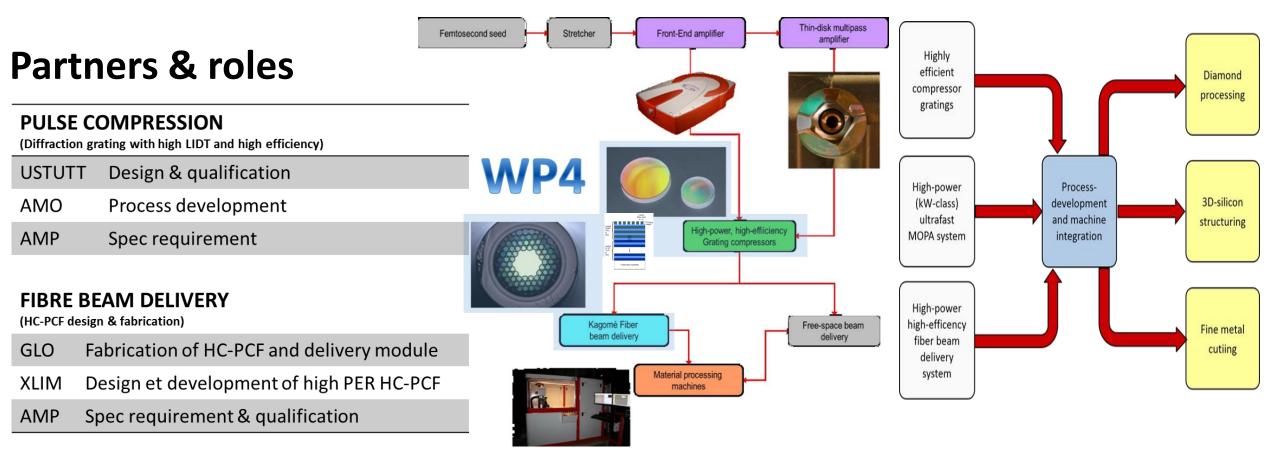
Fetah Benabid

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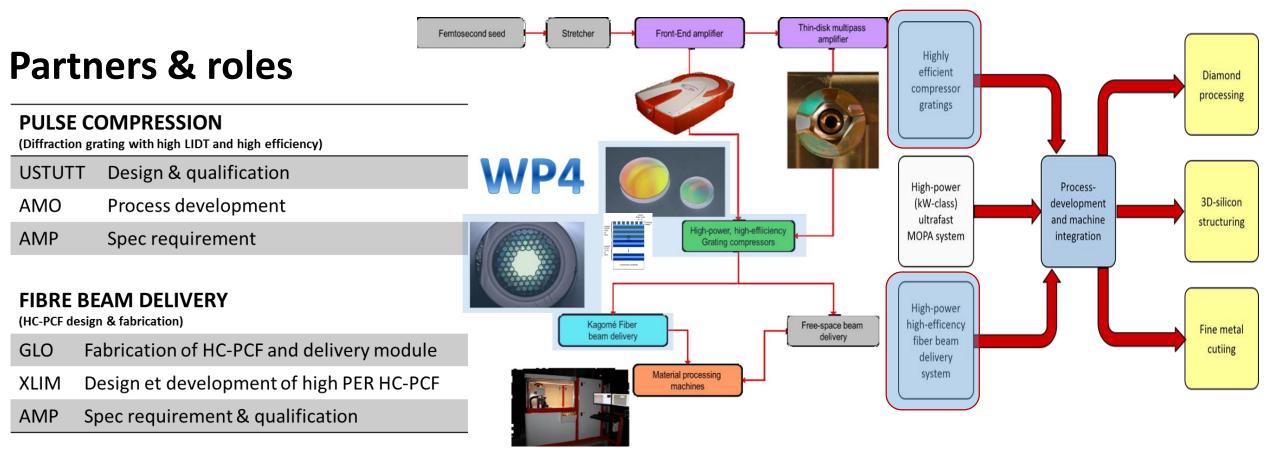
**AIM:** Pulse compression & fibre beam-delivery







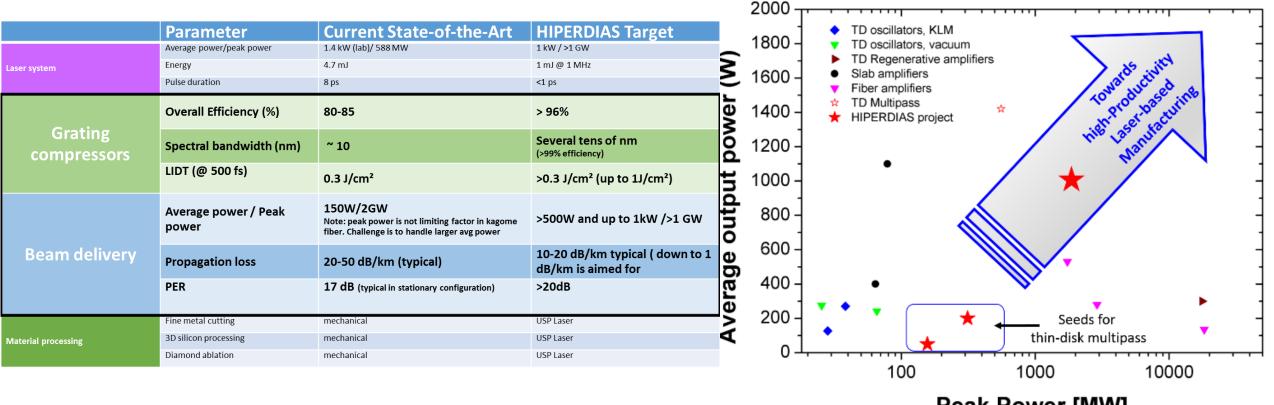
**AIM:** Pulse compression & fibre beam-delivery







#### **AIM:** Pulse compression & fibre beam-delivery



Peak Power [MW]





#### **TASK BREAKDOWN**

6 tasks, 14 Milestones & 7 delivrables

	<b>PULSE COMPRES</b> (Diffraction grating with high LIDT a			FIBRE BEAM DELIVERY (HC-PCF design & fabrication)							
TASK /Leader	Description	Milestones	Deliverables	TASK /Leader	Description	Milestones	Deliverables				
4.1 /USTUTT	Design of grating compressor • <b>Design</b> of the gratings • Parameter space review	M4.1 (M03)	D4.1(M04) D 4.2(M12)	4.4/ GLO	Fabrication & characterization of PMC module for USP fibre- delivery	M 4.1 (M06) M 4.5 (M12,18,28)	D4.4 (M24, M36) D4.7 (M30)				
4.2 /AMO	Development of optimized <b>lithography process</b> for the fabrication of pulse compression gratings			4.5/ GLO	Design and Fabrication of photonic microcell module with integrated coupling optics for fibre-delivery and interface with system	M4.7(M15) M4.9 (M18) M4.10(M24)	D4.6(M30)				
4.3	Development of optimized	M4.3(M08)	M05-M30		integrator.						
/AMO	<b>etching process</b> for the fabrication of pulse compression gratings	n of pulse M4.8(M18)		4.6/ XLIM	Design and Fabrication of high PER HC-PCF for ultra- high energy pulse delivery	M 4.6 (M12) M4.11(M24)	D4.5 (M24)				





WP4 – Task 4.6: Design and fabrication of polarization maintaining hollow-core photonic crystal for ultra-high energy pulse delivery

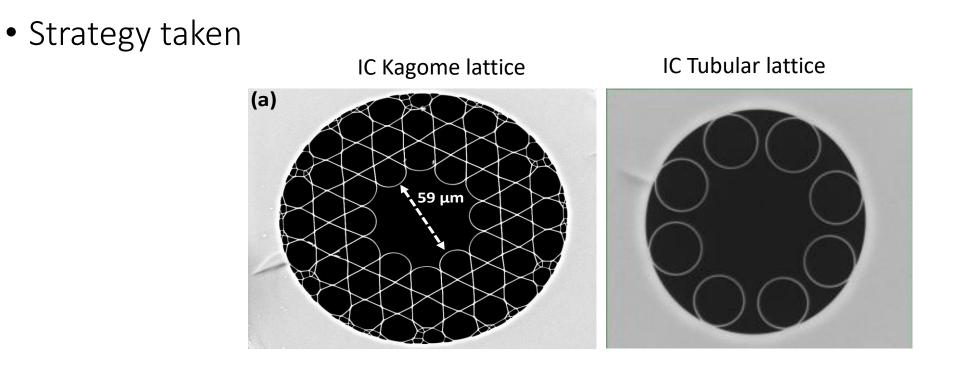
#### • Overview, XLIM, GLO

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NP4 - Photonic components for pre-and-post-pulse conditioning		M	4.1		M4.2	M4.3	ļ.		M4.4 M4.5		M4.7	M4.4 M4.8		_								
T4.1 Design of grating compressors									M4.6			M4.9										
T4.2 Development of a lithography process for the fabrication of pulse compression gratings																						
T4.3 Development of an etching process for the fabrication of optical components																						
T4.4 Fabrication and characterization of photonic microcell (PMC) module			D	4.1					D4.2				D4.3									
T4.5 Design/Fabrication of photonic microcell module with integrated coupling optics																	D	.4				D4.5
T4.6 Design and Fabrication of polarization maintaining hollow-core photonic crystal																	D4	.6				D4.7
1 2) 31	IP4 - Photonic components for pre-and-post-pulse conditioning of grating compressors pment of a lithography process for the fabrication of pulse compression gra pment of an etching process for the fabrication of optical components tion and characterization of photonic microcell (PMC) module /Fabrication of photonic microcell module with integrated coupling optics	IP4 - Photonic components for pre-and-post-pulse conditioning         of grating compressors         pment of a lithography process for the fabrication of pulse compression grating         pment of an etching process for the fabrication of optical components         tion and characterization of photonic microcell (PMC) module         /Fabrication of photonic microcell module with integrated coupling optics	IP4 - Photonic components for pre-and-post-pulse conditioning       w         of grating compressors	IP4 - Photonic components for pre-and-post-pulse conditioning       M4.1         of grating compressors       Image: compression grating set of a lithography process for the fabrication of pulse compression gratings       Image: component set of a lithography process for the fabrication of optical components         pment of an etching process for the fabrication of optical components       Image: component set of a lithography process for the fabrication of optical components         tion and characterization of photonic microcell (PMC) module       Image: component set of photonic microcell module with integrated coupling optics	IP4 - 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- Two fiber designs explored (transmission loss: new records)
- Kagome fiber parameters with PER=21 dB
- Start of the reproducibility and technology transfer to GLOphotonics
- Deviations and proposed corrective actions...
  - NA





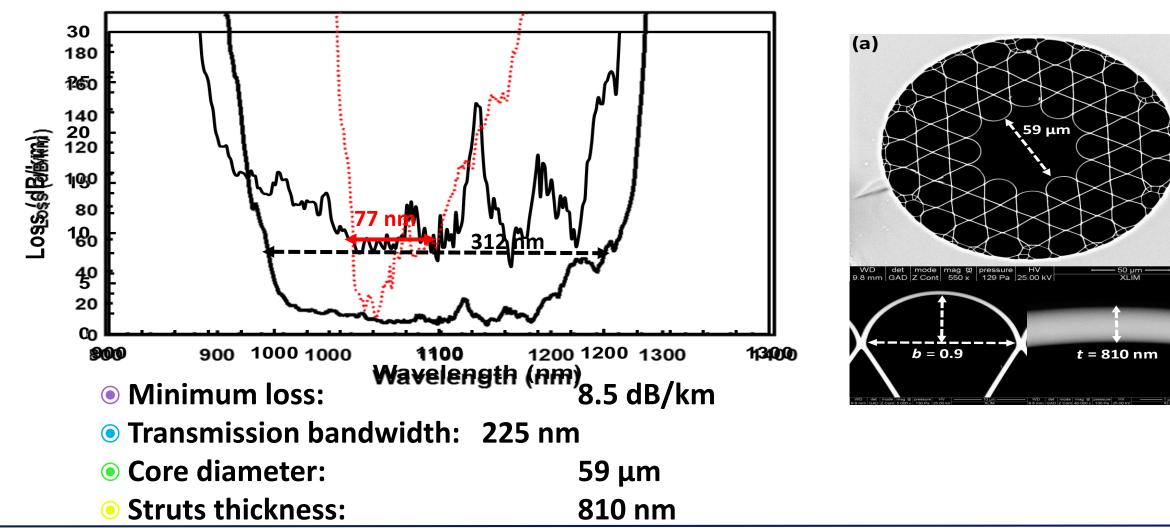


Fine tune the structural parameters of the fibre (strut thickness, contour curvature) to target high PER whilst keeping: ultra-low loss, ultra-low overlap with silica and close to single mode modal content





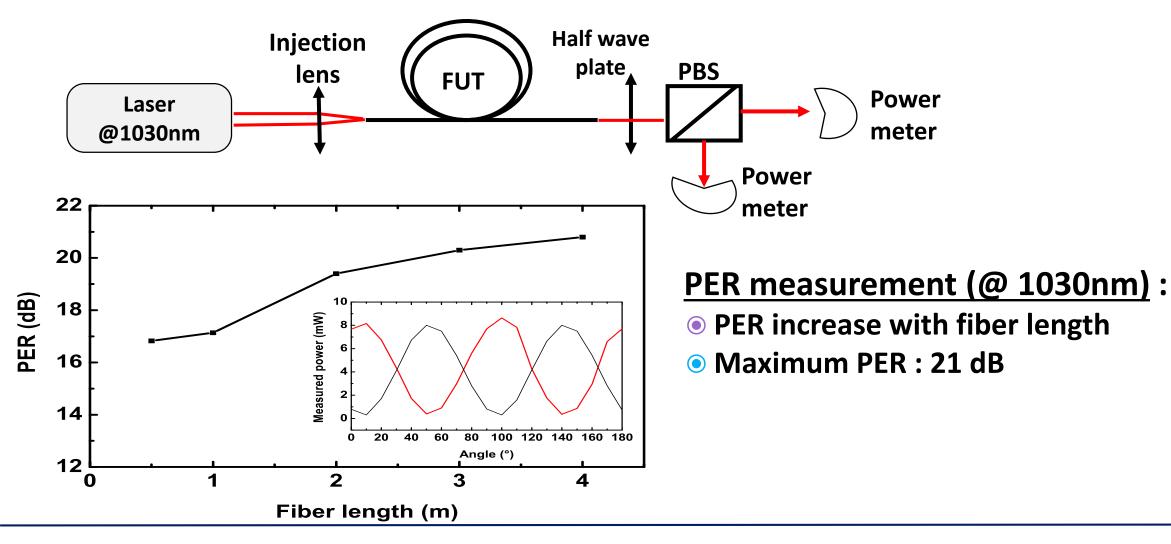
#### **STRUCTURE AND RECORD LOSS**







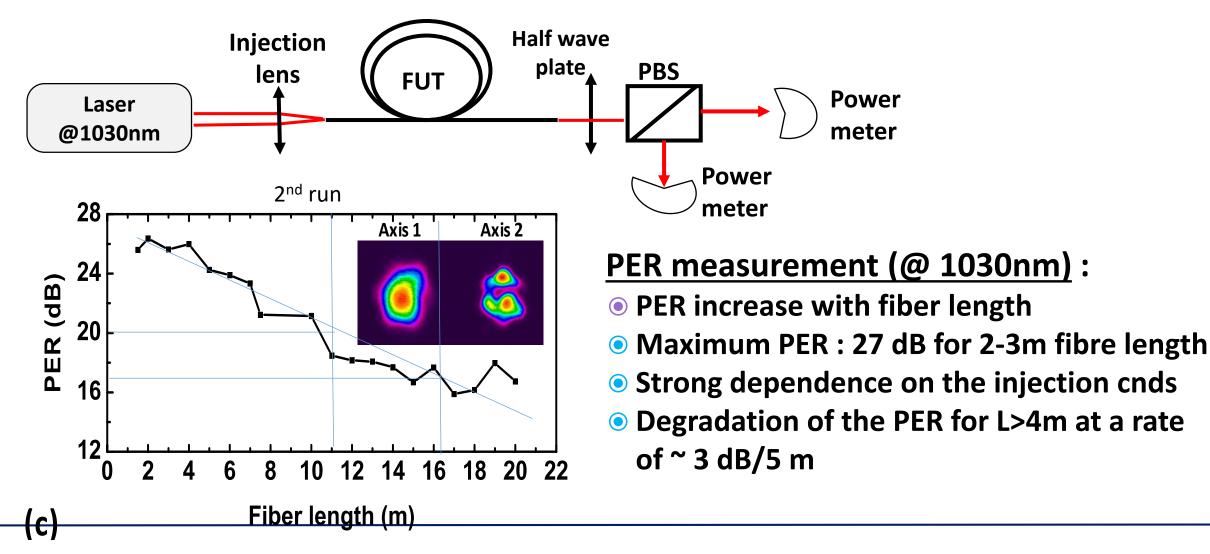
#### **PER** MEASUREMENTS







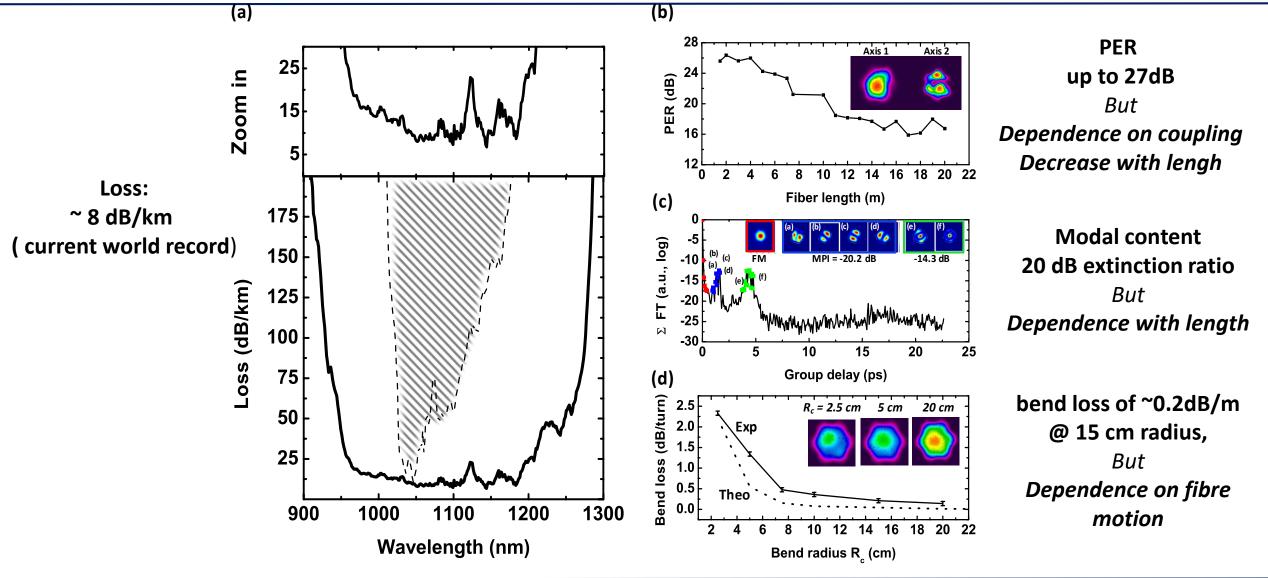
#### **PER** MEASUREMENTS





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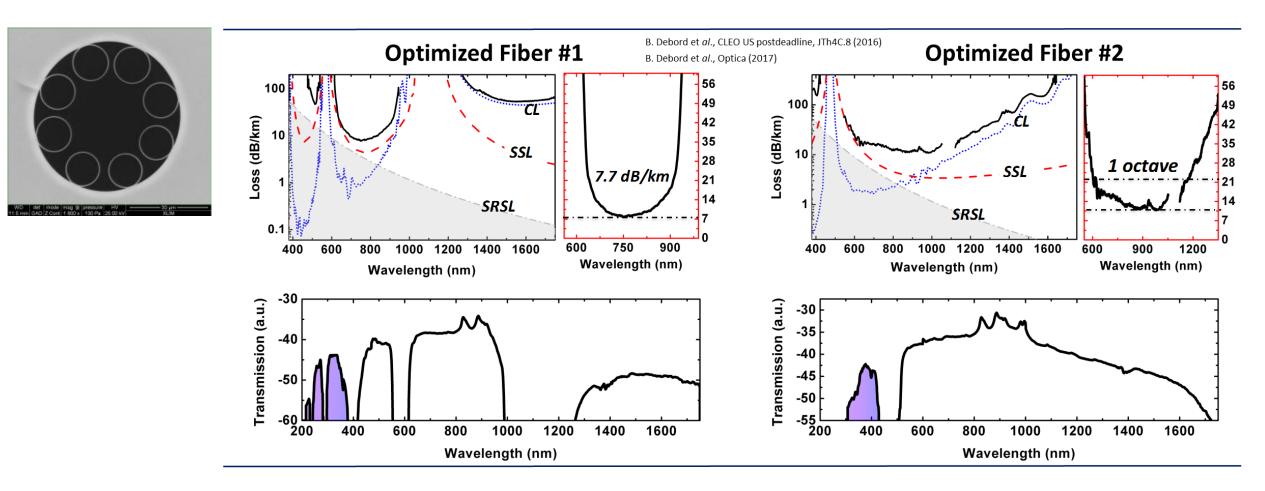




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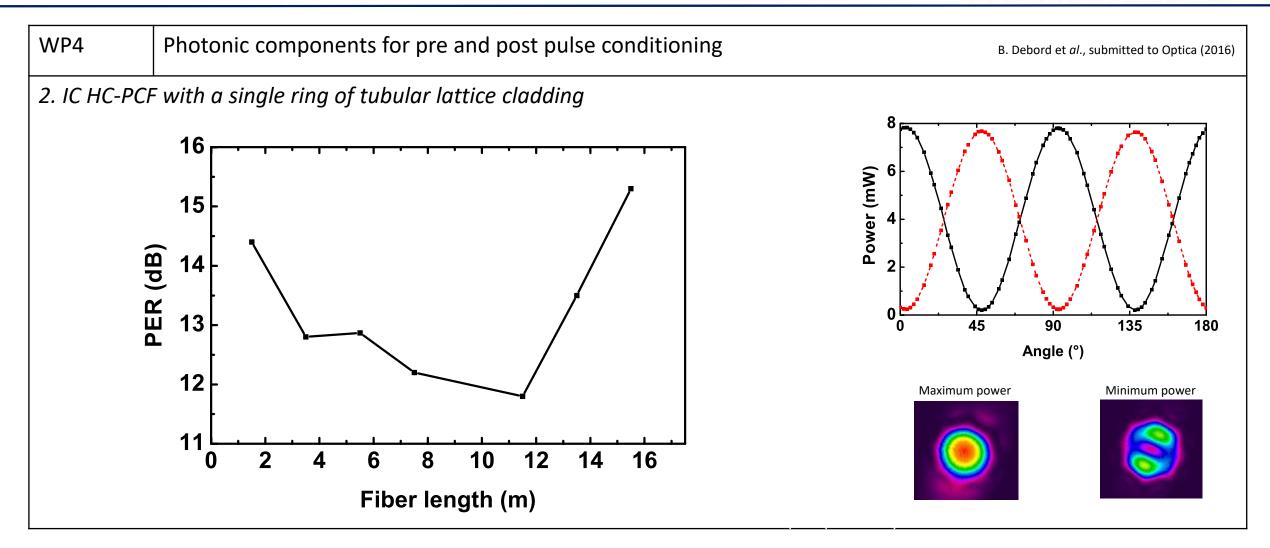


#### **DESIGN #2: TUBULAR LATTICE**





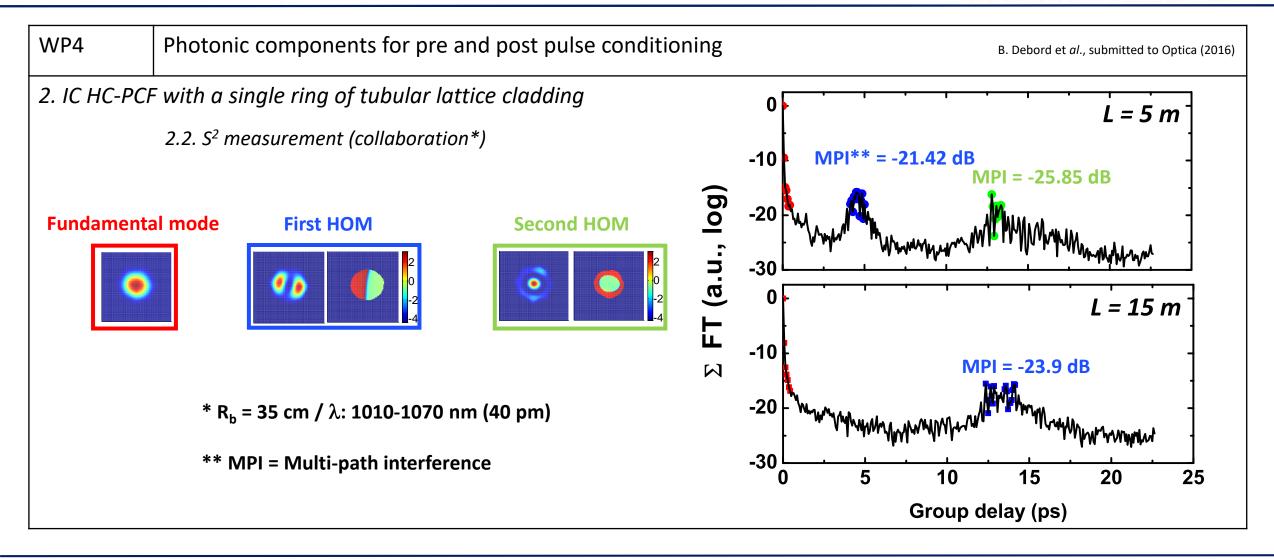










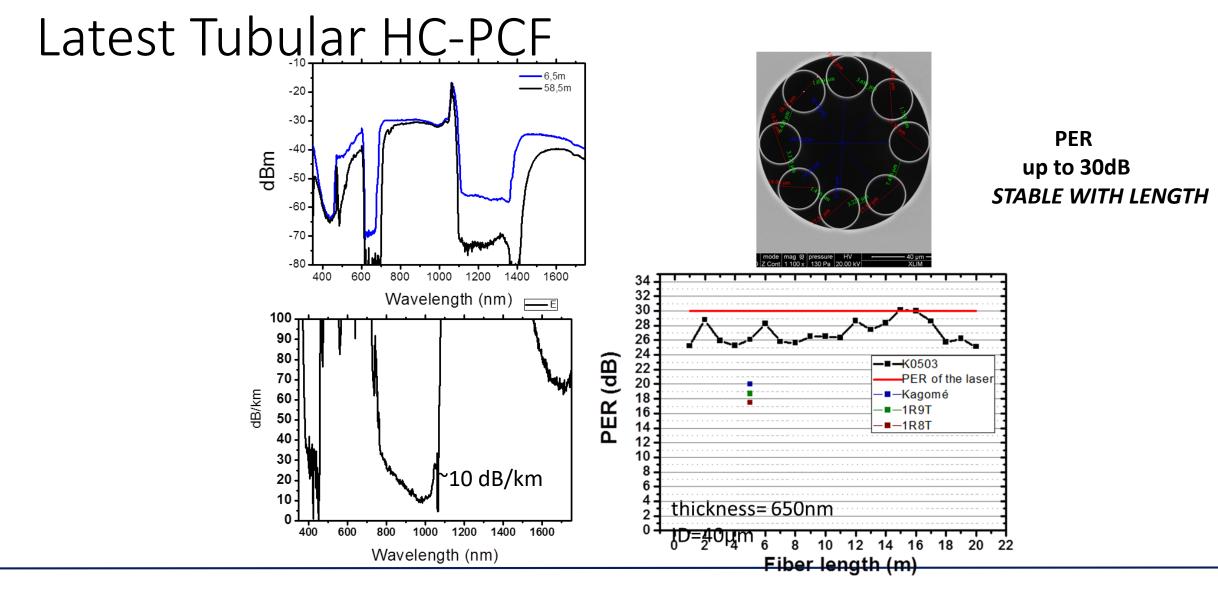






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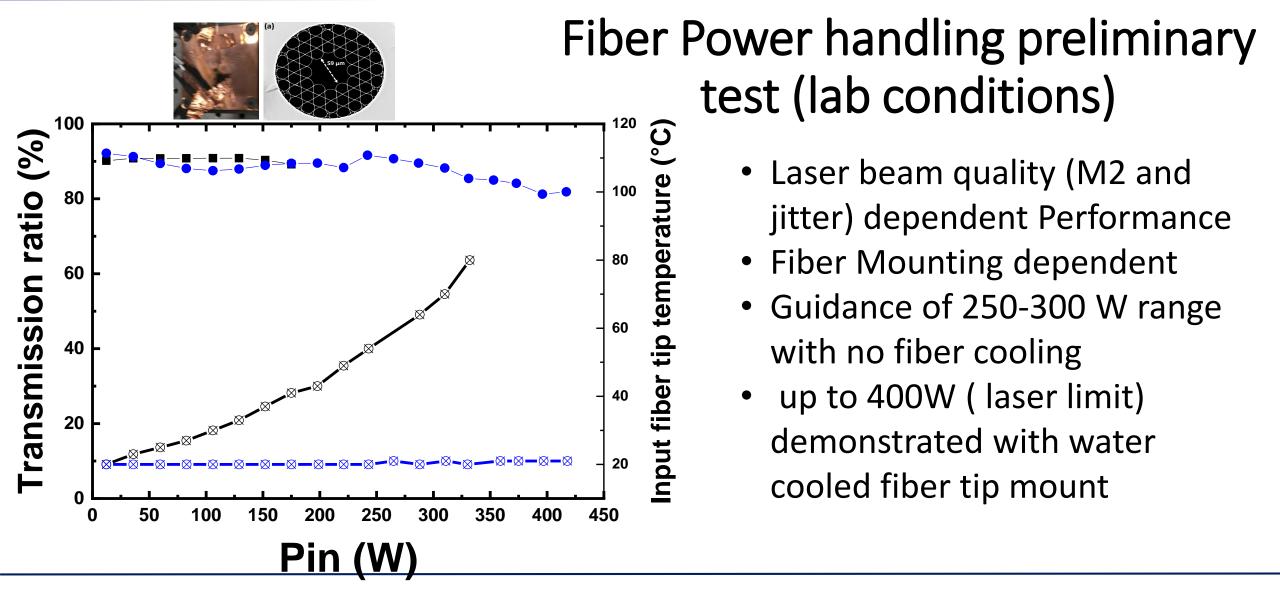


# On going task

- Carry on the characterization of the different fibres:
  - S2 and PER with fibre length, motion, bend.
  - Transfer of « depolarization » upon stress/motion to power fluctuation.
- Reproducibility
  - How loss, PER, MFD, S2, bend loss change from draw to draw
- Technology transfer to GLOphotonics
  - Fibre fabrication and qualification by GLO

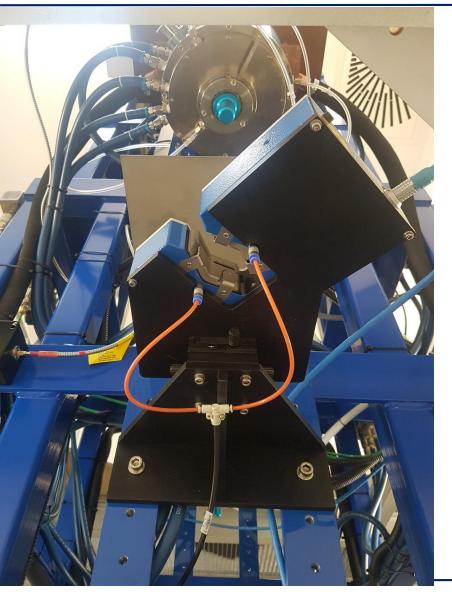












# Installation of GLO new drawing facilities

- Prefrom drawing tower
- Fibre drawing tower
- Double layer coating capabilities
- Clean room and monitered ambient conditions









# Stacking and fibre & preforms pre-processing

- Clean room (ISO7)
- Stacking rigs
- Stocking
- Annealing systems









# Stacking and fibre & preforms pre-processing

- Clean room (ISO7)
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### First test runs & Tech

- **transfer** Cane draw tested/validated
- Std diameter fibre draw tested/validated
- Instrument calibration of IC HCPCF ongoing
- GPPMM fibres qualification to start on Sept. 2018







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## WP4 - Milestones

Milestone title		Due date	Status						
M4.1 First design, high efficient grating mirrors		M03 – April 2016	Fulfilled						
M4.2 PMC module for fiber beam delivery prototype #1		M06 – July 2016	fulfilled						
M4.3 1 <sup>st</sup> generation grating mirror on large area, rectangular substrates fabricated		M08 – September 2016	fulfilled						
M4.4 Fully optical characterization of grating mirror regarding diffraction efficiency and LIDT		M12 – January 2017	Ongoing Diffraction efficiency: fulfilled LIDT: carried out						
M4.5 PMC module for fiber beam delivery prototype #2 PMC module for fiber beam delivery prototype #3 PMC module for fiber beam delivery prototype #4		M12 – January 2017 M18-July2017, M28-May 2018	Fulfilled. Ongoing qualification by AMP & USTUTT						
M4.6 Design of HC-PCF with improved PER at $1\mu m$ (>20 dB)	T4.6	M12 – January 2017	Fulfilled with ongoing characterization and improvement						
M4.7 End-capping definition and process design	T4.5	M15 – April 2017	Partial fulfillment						
M4.8 Demonstration of optimized grating mirrors, 99% DE		M18 – July 2017							
M4.9 End-capped output PMC module for beam delivery	T4.5	M18-July 2017	Partial fulfillment Fulfilled						
M4.10 Qualification of end-capped output PMC module for beam delivery		M24-January 2018	Fulfilled						
M4.11 Fabrication of HC-PCF with improved PER at 1 um (>20 dB)		M24-January 2018	Partial fulfillment Fulfilled						
M4.12 End-capped input PMC module for beam delivery	T4.5	M26-March 2018							





# WP4 - Deliverables

Deliverable title	Due date	Status
D4.1 Report on simulation of pulse compression gratings with diffraction efficiency >=99% over large spectral bandwidth (5 – 10 nm) around 1030 nm	M04 – May 2016	Delivered
D4.2 Report on first fabrication of pulse compression grating with 98% diffraction energy on large area, rectangular substrate material	M12 – January 2017	delivered
D4.3 Report on fabrication and optical characterization of optimized gratings with single-pass diffraction efficiency >=99% over large spectral bandwidth (5 – 10 nm) around 1030 nm	M18 – July 2017	Delivered?
D4.4 (x2) Final version of PMC module for fiber beam delivery	M24-January 2018, M36-January 2019	BDS#1#2 delivrerd
D4.5 End-capped PMC module for beam delivery	M24-January 2018	Delivered
D4.6 HC-PCF with improved PER at 1µm (>20 dB)	M30-July 2018	NA
D4.7 PMC module based on HC-PCF with improved PER at $1\mu m$ (>20 dB)	M30-July 2018	NA





Progress	<ul> <li>GPPMM/XLIM: 2 fibers designs have been explored and fabricated. Both designs show ultra-low transmission loss (&lt;10 dB/km world record). The fibers show PER &gt;20dB for length &lt;10 m and in static configuration, thus fullfiling the project requirements.</li> <li>GLO: Several fiber beam delivery modules has been explored. A design with prelaligned injection head has been developed (BDS). The BDS version 2 has been qualified by AS. BDS with water cooling system has been designed. It is currently under test. Preliminary results show avg power handling up to 400 W. Test are on going and one version is under development to send to C4L.</li> <li>AMO: Lithography/etching process has been defined and developed. Several gratings has been fabricated. Gratings have been fabricated using both processes. Grating depth uniformity has been improved by a factor x2 over(size 70mmx50mm). Diffraction efficiency &gt;99% over an area of 50mmx30mm. Demonstration of damage threshold increase up to 0.3J/cm2.</li> </ul>
Delivrable updates	D4.1: Compressor grating design delivered (USTUT/AMO) D4.2: Lithography process for compression grating delivered (AMO) D4.3: Lithography process for compression grating delivered (AMO) D4.4: Two version of BDS have been developed (GLO). The final version scheduled for M36. D4.6: Two high PER fibers have designed and fabricated (GPPMM/XLIM) D4.7: BDS with high PER fibers scheduled for M30
Next	GPPMM/XLIM: to transfer the fabrication process to GLO. GLO: to fabricate under industrial grade hi-PER HCPCF GLO: To test the power handling of the BDS with water cooling GLO: To make a BDS with hi-PER fibers AMO: Demonstration of the achieved performances with larger areas. Enhancing further the LIDT.